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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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| Sheet | 2 | of | 2 | Attorney Docket Number | 101328-0151 |
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Complete if Known

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| Application Number | 09/851,952-4043 |
| Filing Date | May 9, 2001 |
| First Named Inventor | Theodore H. Fedynyshyn |
| Group Art Unit | 1752 |
| Examiner Name | Not Yet Assigned <i>A. Walker</i> |
| Attorney Docket Number | 101328-0151 |

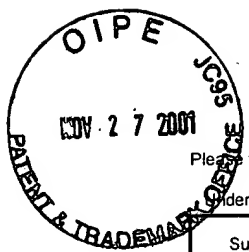
OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS

| Examiner Initials | Cite No. ¹ | Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc), date, page(s), volume-issue number(s), publisher, city and/or country where published. | T ² |
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| Examiner Signature | <i>Shironda C. Walker</i> | Date Considered | <i>August 1, 2002</i> |
|--------------------|---------------------------|-----------------|-----------------------|

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| | | | First Named Inventor | Theodore H. Fedynyshyn | |
| | | | Group Art Unit | 1752 | |
| | | | Examiner Name | Not Yet Assigned <i>A. Wauke</i> | |
| Sheet | 1 | of | 2 | Attorney Docket Number | 101328-0151 |

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| T | | 6037107 | | Thackeray et al. | 03/14/00 | |

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| Examiner Initials* | Cite No. ¹ | Foreign Patent Document | | Name of Patentee or Applicant of Cited Document | Date of Publication of Cited Document MM-DD-YYYY | Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear | T ⁶ |
| | | Office ³ | Number ⁴ <i>(if known)</i> | | | | |
| KW | U | | WO 00/67072 | Feiring et al. | 11/09/00 | | |

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|-----------------------|------------------------|--------------------|-----------------------|
| Examiner Signature | <i>Shanda C. Wauke</i> | Date Considered | <i>August 1, 2002</i> |
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